

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

Application No. : **10/040,042**  
Applicant : **Wei-Yu Su**  
Filed : **November 7, 2001**  
TC/A.U. : **1746**  
Confirmation No. : **1835**  
Title : **Method for Reduction of Photomask Defects**  
Examiner : **El Arini, Zeinab**  
Attorney Docket No : **N1085-90003**  
Customer No. : **08933**

Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

Sir:

**AMENDMENT AND RESPONSE UNDER 37 CFR 1.116(a)**

In response to the Office Action of October 3, 2006, please amend the above-identified application as follows:

**Amendments to the Claims** are reflected in the listing of claims which begins on page 2 of this paper.

**Remarks** begin on page 7 of this paper.